

#13

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE (Rev. 2-32) PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO. 30-4687 (4790)		SERIAL NO.: <div style="font-size: 1.2em;">09/328,646</div>	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)				APPLICANT: SHI-QING WANG, ET AL		FILING DATE: <div style="font-size: 1.2em;">06/09/99</div>	
(Use several sheets if necessary)				GROUP: <div style="font-size: 1.2em;">2811</div>			

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
V _u	AA 5,693,566	12/02/1997	Cheung	437	195	-	
V _u	AB 5,864,172	01/26/1999	Kapoor, et al.	257	634	-	
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS								
							TRANSLATION	
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	NO
V _u	AL	0 680 085 A1	04/28/1995	02/11/95 Europe	-	-	✓	
V _u	AM	0 692 824 A2	07/14/1995	01/17/96 Europe	-	-	✓	
V _u	AN	0 805 491 A2	04/29/1997	05/11/97 Europe	-	-	✓	
V _u	AO	0 849 796 A2	12/16/1997	06/21/98 Europe	-	-	✓	
	AP							
	AQ							

OTHER DOCUMENTS(Including Author, Title, Date, Pertinent Pages, etc.)		
V _u	AR	XP 000300654, Multilevel Interconnection Structure, IBM Technical Disclosure Bulletin, Vol. 34, No. 9, February 1992, P. 220.
V _u	AS	XP 000583029, Low Dielectric Constant Materials for Interlayer Dielectric Applications, Shyam P. Murarka, Solid State Technology, March 1996, No. 3, Tulsa, OK, US, pp 3-7.
V _u	AT	XP 000952344, Processing and Characterization of Silica Xerogel Films for Low-K Dielectric Applications, Anarag Jain, et al., Mat. Res. Soc. Symp. Proc. Vol. 565, 1999, Materials Research Society, pp 8-19.

EXAMINER <u>HUNG K VU</u>	DATE CONSIDERED <u>07/10/01</u>
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Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

#11

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO.: 30-4687 (4790)	SERIAL NO.: 09/328,646 RECEIVED
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		APPLICANT: SHI-QING WANG, ET AL MAY 30 2001	
(Use several sheets if necessary)		FILING DATE: 06/09/01	GROUP: TECHNOLOGY CENTER 2800 2811

U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
Vu	AA	5,858,869	01/12/1999	Chen, et al.	438	597	-
Vu	AB	6,080,526	06/27/2000	Yang, et al.	430	296	-
Vu	AC	6,097,095	08/01/2000	Chung	257	774	-
Vu	AD	6,124,198	09/26/2000	Moslehi	438	622	-
Vu	AE	6,143,641	11/07/2000	Kitch	438	618	-
Vu	AF	6,165,893	12/26/2000	Chung	438	623	-
Vu	AG	6,207,555	03/27/2001	Ross	438	633	-
Vu	AH	6,211,063	04/03/2001	Liu, et al.	438	624	-
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

							TRANSLATION	
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	NO
	AL							
	AM							
	AN							
	AO							
	AP							
	AQ							

OTHER DOCUMENTS(Including Author, Title, Date, Pertinent Pages, etc.)

Vu	AR	"HIGH STUD-TO-LINE CONTACT AREA IN DAMASCENE METAL PROCESSING"; IBM TECHNICAL DISCLOSURE BULLETIN, VOL. 33, NO. 1A, JUNE 1990, PP 160-161.
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EXAMINER HUNG K. VO

DATE CONSIDERED 07/10/01

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(Use several sheets if necessary)				FILING DATE: 06/09/99		GROUP: 2811	

U.S. PATENT DOCUMENTS							
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
✓	AA	5,801,095	9/01/98	YEW, ET AL	438	624	-
	AB						
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FOREIGN PATENT DOCUMENTS								
							TRANSLATION	
		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	YES	NO
	AL							
	AM							
	AN							
	AO							
	AP							
	AQ							

OTHER DOCUMENTS(Including Author, Title, Date, Pertinent Pages, etc.)		
✓	AR	"HIGH STUD-TO-LINE CONTACT AREA IN DAMASCENE METAL PROCESSING"; IBM TECHNICAL DISCLOSURE BULLETIN, VOL. 33, NO. 1A, JUNE 1990, pp. 160-161.
	AS	
	AT	

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